

Application No.: Not Yet Assigned

Docket No.: N9450.0046/P046

REMARKS

The application has been editorially revised for consistency between the specification and the drawings. Favorable action on the application is solicited.

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Respectfully submitted,

By 

Mark J. Thronson

Registration No.: 33,082

DICKSTEIN SHAPIRO MORIN &
OSHINSKY LLP

2101 L Street NW

Washington, DC 20037-1526

(202) 785-9700

Attorneys for Applicant

MARKED-UP VERSION SHOWING CHANGES MADE

[Fig. 4 is a diagram] Figs. 4(a) through 4(c) are diagrams showing an example of patterns suitable for process conditions change monitoring.

[Fig. 5 is a] Figs. 5(a) through 5(c) are cross-sectional [view] views showing an example of patterns suitable for process conditions change monitoring.

[Fig. 6 is a graph] Figs. 6(a) and 6(b) are graphs showing changes in edge width against focus.

[Fig. 7 is another graph] Figs. 7(a) and 7(b) are other graphs showing changes in edge width against focus.

[Fig. 9 is a diagram] Figs. 9(a) and 9(b) are diagrams showing the acquisition of the creation sequences for the models which establish logical linking between exposure conditions and dimensional characteristic quantities.

[Fig. 12 is a diagram] Figs. 12(a) and 12(b) are diagrams of the process conditions change monitoring system pertaining to the third preferred mode of embodiment.

[Fig. 13 is a diagram] Figs. 13(a) and 13(b) are diagrams showing a second example of patterns suitable for process conditions change monitoring.

[Fig. 15 is a diagram] Figs. 15(a) and 15(b) are diagrams showing a third example of patterns suitable for process conditions change monitoring.

[Fig. 16 is a diagram] Figs. 16(a) and 16(b) are diagrams showing the measuring method in the third example of patterns suitable for process conditions change monitoring.

[Fig. 19 is an] Figs. 19 a and 19 b, are epitomic [diagram] diagrams representing the relationship between the cross-sectional shape of a resist pattern and the level of a secondary electron signal.

[Fig. 20 is a graph] Figs. 20 a, and 20 b, are graphs showing the relationship between exposure level, focus, and line width.